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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/766,868	01/30/2004	Takuya Mashimo	248321US-2S CONT	4100
22850 7	590 07/13/2005		EXAMINER	
OBLON, SPIVAK, MCCLELLAND, MAIER & NEUSTADT, P.C. 1940 DUKE STREET			DONG, DALEI	
ALEXANDRL	A, VA 22314		ART UNIT PAPER NUMBER	
		•	2879	
·		DATE MAILED: 07/13/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

·		Application No.	Applicant(s)	
Office Action Summary		10/766,868	MASHIMO ET AL.	(m
		Examiner	Art Unit	<u>M</u>
		Dalei Dong	2879	
Period fo	The MAILING DATE of this communication app or Reply	ears on the cover sheet with the	correspondence address	
THE - Exte after - If the - If NO - Failt Any	MAILING DATE OF THIS COMMUNICATION. Insions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. In period for reply specified above is less than thirty (30) days, a reply of period for reply is specified above, the maximum statutory period ware to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be within the statutory minimum of thirty (30) d will apply and will expire SIX (6) MONTHS fro cause the application to become ABANDON	timely filed ays will be considered timely. m the mailing date of this communication IED (35 U.S.C. § 133).	n.
Status				
•		action is non-final. nce except for formal matters, p		s
Disposit	ion of Claims			
5)□ 6)⊠ 7)□	Claim(s) <u>1-8</u> is/are pending in the application. 4a) Of the above claim(s) is/are withdray Claim(s) is/are allowed. Claim(s) <u>1-8</u> is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and/or			
Applicat	ion Papers			
10)⊠	The specification is objected to by the Examine The drawing(s) filed on 30 January 2004 is/are: Applicant may not request that any objection to the Replacement drawing sheet(s) including the correction The oath or declaration is objected to by the Examine	a)⊠ accepted or b)⊡ objected or b) objected or b) objected drawing(s) be held in abeyance. So ion is required if the drawing(s) is c	ee 37 CFR 1.85(a). Objected to. See 37 CFR 1.121(d	d).
Priority (under 35 U.S.C. § 119			
a)	Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau See the attached detailed Office action for a list of	s have been received. s have been received in Applica ity documents have been recei ı (PCT Rule 17.2(a)).	ation No ved in this National Stage	
	ot(s) te of References Cited (PTO-892) te of Draftsperson's Patent Drawing Review (PTO-948)	4) Interview Summa Paper No(s)/Mail		
3) 🛛 Infor	mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) or No(s)/Mail Date 1/30/2004.		Patent Application (PTO-152)	

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DETAILED ACTION

Priority

1. Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

Specification

2. Applicant is reminded of the proper language and format for an abstract of the disclosure.

The abstract should be in narrative form and generally limited to a single paragraph on a separate sheet within the range of 50 to 150 words. It is important that the abstract not exceed 150 words in length since the space provided for the abstract on the computer tape used by the printer is limited. The form and legal phraseology often used in patent claims, such as "means" and "said," should be avoided. The abstract should describe the disclosure sufficiently to assist readers in deciding whether there is a need for consulting the full patent text for details.

The language should be clear and concise and should not repeat information given in the title. It should avoid using phrases which can be implied, such as, "The disclosure concerns," "The disclosure defined by this invention," "The disclosure describes," etc.

3. The disclosure is objected to because of the following informalities:

On page 12 of the Disclosure, line 4, "rectangular smaller hole 22" should be changed to "rectangular smaller hole 19b".

Appropriate correction is required.

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Claim Rejections - 35 USC § 102

4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

5. Claims 1-4 are rejected under 35 U.S.C. 102(b) as being anticipated by U.S. Patent No. 4,996,458 to Hattori.

Regarding to claim 1, Hattori discloses in Figures 1-4 and 25, a color cathode ray tube comprising: a panel (2) having a phosphor screen (3) on an inner surface thereof; an electron gun (12) which emits electron beams (6) toward the phosphor screen (3); and a substantially rectangular shadow mask (7) located opposite the phosphor screen (3) inside the panel (2) and having a major axis and a minor axis extending at right angles to each other and to a tube axis, the shadow mask (7) including a main mask (21) opposed substantially to the whole surface of the phosphor screen (3) and having a substantially rectangular effective portion formed with a number of electron beam passage apertures (13a) and a belt-shaped auxiliary mask (22) fixed to a region containing the minor axis of the effective portion of the main mask (21), having a number of electron beam passage apertures (13b) corresponding individually to the electron beam passage apertures (13b) of the main mask (21), and elongated along the minor axis, each of the electron beam apertures (13b) of the auxiliary mask (22) being a communicating hole formed of a substantially rectangular smaller hole opening in that surface of the auxiliary mask which

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is in contact with the main mask (21) and a substantially rectangular larger hole opening in the opposite surface of the auxiliary mask (22), and the smaller and larger holes of each electron beam passage aperture (13b) of the auxiliary mask (22) individually having central axes extending coaxially with each other and substantially at right angles to the surface of the auxiliary mask (22) in the direction of the major axis.

Regarding to claim 2, Hattori discloses in Figures 1-4 and 25, the electron beam passage apertures (13) of the main mask (21) and the auxiliary mask (22) are arranged at pitches of about 0.4 mm to 0.6 mm in the direction of the major axis (see column 12, line 67 to column 13, line 20).

Regarding to claim 3, Hattori discloses in Figures 1-4 and 25, the region of the auxiliary mask (22) which is situated between the electron beam passage apertures (13b) adjoining one another in the direction of the major axis id welded (W or 32) to the main mask (21).

Regarding to claim 4, Hattori discloses in Figures 1-4 and 25, the region of the auxiliary mask (22) which is situated between the electron beam passage apertures (13b) adjoining one another in the direction of the major axis id welded (W or 32) to the main mask (21).

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Claim Rejections - 35 USC § 103

6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 6. Claims 5-8 are rejected under 35 U.S.C. 103(a) as being unpatentable over U.S. Patent No. 4,996,458 to Hattori.

Regarding to claim 5, a color cathode ray tube comprising: a panel (2) having a phosphor screen (3) on an inner surface thereof; an electron gun (12) which emits electron beams (6) toward the phosphor screen (3); and a substantially rectangular shadow mask (7) located opposite the phosphor screen (3) inside the panel (2) and having a major axis and a minor axis extending at right angles to each other and to a tube axis, the shadow mask (7) including a main mask (21) opposed substantially to the whole surface of the phosphor screen (3) and having a substantially rectangular effective portion formed with a number of electron beam passage apertures (13a) and a belt-shaped auxiliary mask (22) fixed to a region containing the minor axis of the effective portion of the main mask (21), having a number of electron beam passage apertures (13b) corresponding individually to the electron beam passage apertures (13b) of the main mask (21), and elongated along the minor axis, each of the electron beam apertures (13b) of the auxiliary mask (22) being a communicating hole formed of a substantially rectangular smaller hole opening in that surface of the auxiliary mask which is in contact

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with the main mask (21) and a substantially rectangular larger hole opening in the opposite surface of the auxiliary mask (22), the electron beam passage apertures of the auxiliary mask having relationships: Da (OW1 + OW2) / Db (OW3 + OW4) = 0.64 and Da < Db, where Da and Db are the diameter of the smaller hole in the direction of the major axis and the diameter of the larger hole in the direction of the major axis, respectively, and the smaller and larger holes of each electron beam passage aperture (13b) of the auxiliary mask (22) individually having central axes extending coaxially with each other and substantially at right angles to the surface of the auxiliary mask (22) in the direction of the major axis.

However, Hattori does not specifically discloses the relationships of Da / Db is greater than or equal to 0.7.

Hattori discloses the relationship of Da (OW1 + OW2) / Db (OW3 + OW4) = 0.64 (see column 13, lines 20-43) for the purpose of eliminating any possible variation in the surface area for the passage of the electron beams.

Thus, it would have been obvious to one having ordinary skill in the art at the time the invention was made to have made the electron beam passage apertures of the auxiliary mask of Hattori having the relationship of Da / Db is greater than or equal to 0.7 in order to eliminate any possible variation in the surface area for the passage of the electron beams. Furthermore, it has been held that where the general conditions of a claim are disclosed in the prior art, discovering the optimum or workable ranges involves only routine skill in the art.

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Regarding to claim 6, Hattori discloses in Figures 1-4 and 25, the electron beam passage apertures (13) of the main mask (21) and the auxiliary mask (22) are arranged at pitches of about 0.4 mm to 0.6 mm in the direction of the major axis (see column 12, line 67 to column 13, line 20).

Regarding to claim 7, Hattori discloses in Figures 1-4 and 25, the region of the auxiliary mask (22) which is situated between the electron beam passage apertures (13b) adjoining one another in the direction of the major axis id welded (W or 32) to the main mask (21).

Regarding to claim 8, Hattori discloses in Figures 1-4 and 25, the region of the auxiliary mask (22) which is situated between the electron beam passage apertures (13b) adjoining one another in the direction of the major axis id welded (W or 32) to the main mask (21).

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's 7. disclosure.

The following prior art are cited to further show the state of the art of composition of a color cathode ray tube.

U.S. Patent No. 5,079,477 to Yamamoto.

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- U.S. Patent No. 5,180,322 to Yamamoto.
- U.S. Patent No. 5,635,320 to Ohtake.
- U.S. Patent No. 5,686,784 to Thoms.
- U.S. Patent No. 6,577,047 to Ohmae.
- U.S. Patent No. 6,803,713 to Takahashi.
- U.S. Patent No. 6,894,444 to Nakayama.
- U.S. Patent Application No. 2004/0256970 to Takahashi.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Dalei Dong whose telephone number is (571)272-2370. The examiner can normally be reached on 8 A.M. to 5 P.M..

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nimeshkumar Patel can be reached on (571)272-2457. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

D.D.

July 5, 2005

Joseph Williams Primary Examiner Art Unit 2879

Josephille

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